

## Development of Carbon Nanotube Field-Effect Transistors for Use in Next Generation Electronics

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### Abstract:

Due to its exceptional electronic properties, the carbon nanotube field-effect transistor (CNTFET) is a promising alternative to the traditional metal-oxide-semiconductor field-effect transistor (MOSFET) used in current devices, replacing the channel material in MOSFETs with thin carbon nanotubes with diameters of 1-2 nm. Because various difficulties have arisen in the mass production of reliable CNTFETs, this project aimed to fabricate and analyze the efficiency of a number of these devices, examining the viability of their optimization for industrial applications. Spinning solutions that were specifically sorted for a high concentration of semiconducting CNTs onto silicon substrates, we then located these tubes on an atomic force microscope (AFM). The devices were manufactured through electron beam (e-beam) lithography and deposition. We applied test voltages between the source and drain of these devices and observed the amount of current flowing through the channels with respect to the backgate voltage. Insights gained as a result of these experiments will have a significant impact on the performance and power of future electronic devices.

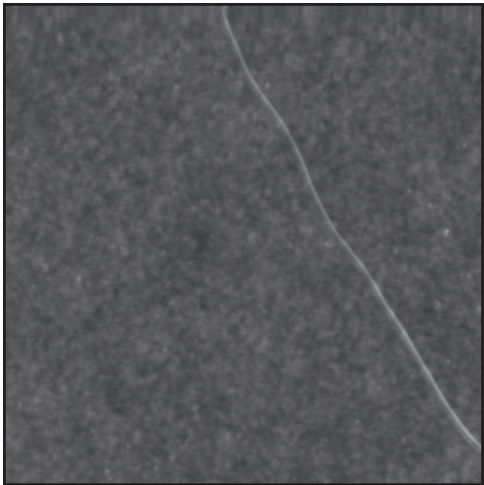


Figure 1: 1 μm × 1 μm image of a carbon nanotube as seen under an AFM.

### Introduction:

For more than 40 years, Moore's Law has held true in that the number of transistors on a chip doubles approximately every two years. However, an increase in the transistor count must lead to a decrease in transistor size, and serious limitations of current fabrication technology are faced at the sub-22 nm range. Since Intel, a world leader in the semiconductor industry, has already begun processing at the 32 nm scale in 2010, the success of predictions made by Moore's Law may soon reach an end. CNTFETs provide a possible alternative in that they have near ballistic transport (minimal electron scattering) and much higher electron mobility than silicon (up to 70 times) [1]. However, challenges in their fabrication still exist, which includes the separation of metallic and semiconducting nanotubes in the same mixture and having a wide range of diameter in CNTs found in the mixture, which affects their electronic properties.

The Shinohara group from Japan has been working on a separation method known as multicolumn gel chromatography. This method is based on the structure dependent interaction strength of CNTs with an allyl dextran based gel. There are multiple columns of gel and the CNT solution is dispersed (using a surfactant called SDS) on the top of the first column. The absorption site at this column is fully occupied by nanotubes that exhibit the strongest interaction with the gel and the rest of the solution moves on



Figure 2: Image of actual device as seen under a probe station.

